Picosun P-300BV Pro ALD system

Model: P300BV

Maker: Picosun

ITEM	QTY	DESCRIPTION
Reactor	1	PICOSUN™ P-300BV Pro ALD reactor with four separate precursor inlets, each with own MFC, pulsing valve and PT. Maximum deposition temperature of the ALD reactor is 500 °C. The Product includes:
		✓ Vacuum chamber (AISI304)
		Stainless steel vessel with KF connection flanges
		✓ Reaction chamber (AISI316L) RC-300 (4 inlets)
		Chamber and lid with top flow precursor distribution geometry
		✓ Sample holder for max 150mm*25 wafers
		✓ Pro source control and electronics system
Software	1	Pro software with a touch panel PC Touch panel PC and electronics cabinet used for operating the ALD reactor with ALD-software and electronics. Can also monitor the tool during deposition and store recipes.
Precursor sources	4	3 Picosolution™ 600 source systems for high vapor pressure liquid precursors for e.g. Al ₂ O ₃ , Water and TiO ₂ .
		1 Picohot™ 300 heated source system for low vapor pressure precursors, e.g. SiO₂
		Each precursor line is connected to a carrier/purge nitrogen line.
Picozone Ozone Generator	1	PZ-200 Sumitomo Ozone Generator and PicoGas™ source line connections, MFM, gauge and control interfaces.
Vacuum pump	1	Edward iXH610 dry vacuum pump, afterburner and a mechanical foreline particle trap included.
PicoLoader	1	The Hineloader for cassette transfer for 150mm*25 wafers
	1	Scroll Pump (Edwards nXDS10i 11.4 m3/h) with ultimate pressure at 7x10-3 mBar
Warranty	1	12 months warranty after tool acceptance.
Commissioning, installation and user training	1	Commissioning (installation, including acceptance tests). Basic user training for the equipment during installation, for any number of people is included in the price.

Facilities requirements, supplied by the Buyer: Electricity, leak tester with helium, chemicals, pump lines, pump exhaust line, gas lines, compressed dry air (4–5.5 barg pressure), cooling water (for the plasma generator and dry pump), argon line (for plasma generator) and nitrogen line (min. 2/50 slm flow, 99.999 % min. purity (99.9999 % for nitrides), 1-2 barg pressure for the ALD unit and the dry pump.

